

| | | | |
|----------------------------------------------------------|--|----------------------------|------------|
| U.S. Department of Commerce, Patent and Trademark Office | | Atty Docket No. | Serial No. |
| | | M-10700 US | 09/741,663 |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | Applicant(s) | |
| (Use several sheets if necessary) | | Andrei V. Shchegrov et al. | |
| | | Filing Date | Group |
| | | December 19, 2000 | 2877 |

U.S. Patent Documents

| *Examiner Initial | | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
|-------------------|----|-----------------|---------|------------|-------|----------|----------------------------|
| <i>QW</i> | AA | 5,751,427 | 5/12/98 | de Groot | | | |
| <i>QW</i> | AB | 6,268,916 | 7/31/01 | Lee et al. | | | |
| | AC | | | | | | |
| | AD | | | | | | |
| | AE | | | | | | |
| | AF | | | | | | |
| | AG | | | | | | |
| | AH | | | | | | |
| | AI | | | | | | |
| | AJ | | | | | | |
| | AK | | | | | | |

Foreign Patent Documents

| | | | | | | | Translation | |
|--|----|----------|------|---------|-------|----------|-------------|----|
| | | Document | Date | Country | Class | Subclass | Yes | No |
| | AL | | | | | | | |
| | AM | | | | | | | |
| | AN | | | | | | | |
| | AO | | | | | | | |
| | AP | | | | | | | |

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

| | | |
|-----------|----|--------------------------------------------------------------------------------------------------------|
| <i>QW</i> | AQ | International Search Report for corresponding PCT application No. PCT/US01/49001 dated April 18, 2002. |
| | AR | |
| | AS | |

Examiner

[Signature]

Date Considered

03/18/2004

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

| | | | | | | | | |
|----------------------------------------------------------|--|--|--|--|---------------------|--|------------|--|
| U.S. Department of Commerce, Patent and Trademark Office | | | | | Atty Docket No. | | Serial No. | |
| | | | | | M-10700 US | | 09/741.663 | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | | | | Applicant(s) | | | |
| (Use several sheets if necessary) | | | | | ANDREI V. SHCHEGROV | | | |
| | | | | | Filing Date | | Group | |
| | | | | | December 19, 2000 | | 2877 | |

(Stamp: AUG 30 2001)

| U.S. Patent Documents | | | | | | | |
|-----------------------|----|-----------------|---------|---------------|-------|----------|----------------------------|
| *Examiner Initial | | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
| <i>SW</i> | AA | 5,963,329 | 10/5/99 | Conrad et al. | 356 | 372 | 10/31/97 |
| | AB | | | | | | |
| | AC | | | | | | |
| | AD | | | | | | |
| | AE | | | | | | |
| | AF | | | | | | |
| | AG | | | | | | |
| | AH | | | | | | |
| | AI | | | | | | |
| | AJ | | | | | | |
| | AK | | | | | | |

| Foreign Patent Documents | | | | | | | Translation | |
|--------------------------|----|----------|------|---------|-------|----------|-------------|----|
| | | Document | Date | Country | Class | Subclass | Yes | No |
| | AL | | | | | | | |
| | AM | | | | | | | |
| | AN | | | | | | | |
| | AO | | | | | | | |
| | AP | | | | | | | |

| OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) | |
|------------------------------------------------------------------|--------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|
| <i>/</i> | AQ Patent Search conducted on August 1, 2000 |
| <i>/</i> | AR "Ultraviolet-visible ellipsometry for process control during the etching of submicrometer features," N. Blayo et al., <i>J. Opt. Soc. Am. A.</i> , Vol. 12, No. 3, March 1995, pp. 591-599 |
| <i>/</i> | AS "Algorithm Implementation and Techniques for Providing More Reliable Overlay Measurements and Better Tracking of the Shallow Trench Isolation (STI) Process," D. Schramm et al., <i>SPIE: Conference on Metrology, Inspection, and Process Control of Microlithography XIII</i> , March 1999, pp. 116-122 |
| Examiner <i>[Signature]</i> | Date Considered <i>03/18/2004</i> |

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.